



**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

**Applicant(s):** Douglas D. Coolbaugh, et al. **Examiner:** Unassigned

**Serial No:** 10/605,439

**Art Unit:** Unassigned

**Filed:** 9/30/03

**Docket:** BUR920020094US1 (16895)

**For:** PRECISION POLYSILICON  
RESISTOR PROCESS

**Dated:** 11/13/03

Commissioner for Patents  
United States Patent Office  
Alexandria, VA 22313-1450

**SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT**

Sir:

In accordance with 37 C.F.R. §§ 1.97 and 1.98, it is requested that the following references, which are also listed on the attached Form PTO-1449, be made of record in the above-identified case.

1. Japanese Patent Publication No. JP5275619, dated October 22, 1993;
2. C.H. Lee, IBM Disclosure Bulletin "Polysilicon Resistors Compatible with Bipolar Integrated Circuits and Method of Manufacture", Vol. 25, No. 5, October 1982;  
and
3. G.R. Goth, et al., IBM Disclosure Bulletin "Planar Self-Aligned Metal/Sidewall and Polysilicon-Resistor Process", Vol. 25, No. 2, July 1982.

---

**CERTIFICATE OF MAILING UNDER 37 C.F.R. §1.8(a)**

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner for Patents, Box 1450, Alexandria, VA 22313-1450 on

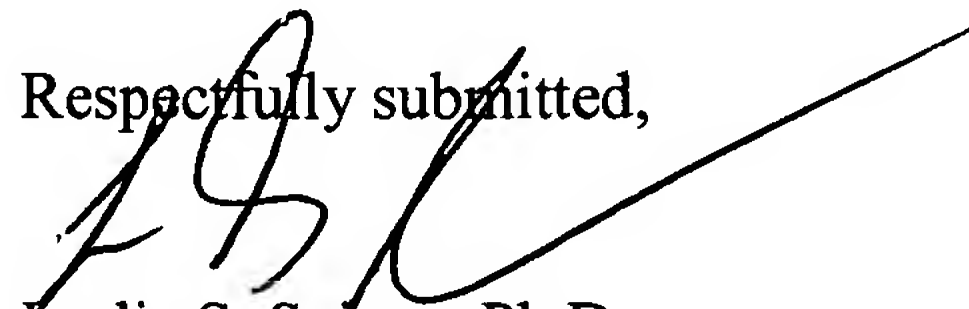
**Dated:** 11/13/03

*Maryann Lusi*  
Maryann Lusi

Applicants are submitting copies of the above-cited references.

Inasmuch as this Information Disclosure Statement is being submitted in accordance with the schedule set out in 37 C.F.R. § 1.97(b), no statement or fee is required.

Respectfully submitted,



Leslie S. Szivos, Ph.D.

Registration No.: 39,394

Scully, Scott, Murphy & Presser  
400 Garden City Plaza  
Garden City, New York 11530  
(516) 742-4343

Enclosure      PTO 1449  
Three (3) references

\* **EXAMINER:** Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.